



# Optical Technology and Measurement for Industrial Applications Conference (OTM25)

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Papers on the following and related topics are solicited for this conference:

- 3D profilometry
- polarimetry/ellipsometry
- novel optical testing
- surface inspection methods and applications
- absolute testing for metrology
- application of interferometric techniques
- machine/robot vision methods, architectures and applications
- lighting methods and systems for inspection
- dynamic measurement
- unique optical systems for inspection and measurements
- 2D and 3D machine vision methods and applications
- 3D data acquisition
- freeform testing
- scatterometry
- unconventional microscope for inspection
- super-high accurate measurement for smooth surfaces
- micro- and nano-scale measurement methods
- structured light methods, fringe projection measurement and applications
- phase shifting methods applied to industrial inspection
- mechanic-optics and photonics for metrology and inspection
- optical inspection by optical comb
- super resolution microscope for inspection
- spherical and aspherical measurements
- color metrology of manufactured goods
- on-line and process control measurements
- on-machine tool measurements of shape and finish
- high-resolution and high-speed inspection applications
- novel interferometry.

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